

FORM PTO-1449 (REV.7-80)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. 10/620,782		APPLICATION NO. 501085.02	
INFORMATION DISCLOSURE STATEMENT <i>(Use several sheets if necessary)</i>				APPLICANT(S) Dirk J. Sundt et al.			
				FILING DATE July 15, 2003		GROUP ART UNIT Not Yet Assigned	

U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
	AA	6,177,331 B1	01/23/01	Koga	438	424	
	AB	6,548,371 B2	04/15/03	Fujimaki	438	424	
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						

FOREIGN PATENT DOCUMENTS							
DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION		
					YES	NO	
AK							
AL							
AM							
AN							
AO							

OTHER PRIOR ART <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>	
	AP Cheung, N., Lecture notes (handout) EE 143, Lecture 15, University of California Berkely, 2000.
	AQ Clark, S., "Chemical Etching of Silicon Nitride (Si3N4) with Hot Phosphoric Acid (H3PO4)", Bold Technologies Technical Paper, 2000, pp. 1-6.
	AR

EXAMINER 	DATE CONSIDERED 09/09/04
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* EXAMINER: Initial if reference considered, whether or not criteria is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant(s).